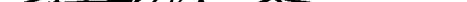


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Substitute for Form 1449A/PTO		<i>Complete if Known</i>		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		Application Number	10/635,344	
		Filing Date	August 6, 2003	
		First Named Inventor	Alan E. Delahoy et al.	
		Group Art Unit	1753	
		Examiner Name	Unknown — VerSteeg	
Serial Number	of	2	Attorney Docket Number	ENPI 0101 PUS

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

Examiner Signature		Date Considered	April 14, 2005
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document.

³ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. * Applicant is to place a check mark here if English language Translation is attached.

Substitute for Form 1449B/PTO				Complete if Known	
				Application Number	10/635,344
				Filing Date	August 6, 2003
				First Named Inventor	Alan E. Delahoy et al.
				Group Art Unit	1753
				Examiner Name	Unknown VerSteeg
Sheet	1	of	2	Attorney Docket Number	

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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18-205

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
SHV		"Deposition Schemes for Low Cost Transparent Conductors for Photovoltaics", A.E. Delahoy & M. Cherny, Mat. Res. Symp. Proc., Vol. 426, 1996, pgs. 467-477	
SHV		"High-Rate Low Kinetic Energy Gas-Flow-Sputtering System", K. Ishii, J. Vac. Sci. Technol. A, Vol. 7, No. 2, 1989, pgs. 256-258	
SHV		"Hollow Cathode Discharge Sputtering Device for Uniform Large Area Thin Film Deposition", H. Koch, J. Vac. Sci. Technol. A., Vol. 9, No. 4, 1991, pgs. 2374-2377	
SHV		"Zirconia Thin Film Deposition on Silicon by Reactive Gas Flow Sputtering: The Influence of Low Energy Particle Bombardment", T. Jung & A. Westphal, Mater. Sci. Eng., A140, 1991, pgs. 528-533	
SHV		"High Rate Deposition of Alumina Films by Reactive Gas Flow Sputtering", T. Jung & A. Westphal, Surf. Coat. Technol., 59, 1993, pgs. 171-176	
SHV		"Gas Flow Sputtering of Oxide Coatings: Practical Aspects of the Process", Th. Jung, T. Kälber, V.v.d. Heide, Surf. Coat. Technol., 86-87, 1996, pgs. 218-224	
SHV		"New DC Sputter Sources for the Large Scale Deposition of Oxide Films", M. Höfer, A. Jung, T. Jung, H.-U. Kricheldorf & F. Schmidt, Proc. 43 rd SVC Annual Tech. Conf., 2000, pgs. 287-292	

Examiner Signature		Date Considered	April 14, 2005
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